

Call for Papers
for a special issue of *Microelectronic Engineering*

Micro- and Nano-Patterning
Short title: μ nP 2015

including selected papers of the
41st Micro and Nano Engineering conference [MNE 2015](#)

The aim of this special issue is to bring together recent advances in Micro- and Nano-Patterning. This issue is 'open call'. This means that, while mainly including selected papers presented at MNE 2015, it is also open to other authors.

The MNE conference series focuses on micro- & nanofabrication and manufacturing using lithography and other approaches related to micro- and nano-patterning, as well as the application of micro- and nanostructures and devices in electronics, photonics, electromechanics, environment, life sciences and biology.

The areas of particular interest for this special issue are:

Micro- and Nano-Patterning

- **Photon lithography:** DUV, EUV, immersion, sources, optics, mask technology, alignment, optical proximity correction, modelling, throughput, multiple exposure
- **Electron and ion beam lithography:** sources, optics, systems, alignment, proximity, corrections, modelling, ion and electron beam - surface interactions, direct write, mask fabrication
- **Other patterning techniques:** soft lithography, nano-imprint, contact printing, stencil based patterning, directed self-assembly, tip- and scanning-probe-based techniques, novel techniques
- **Materials for micro- and nano-patterning:** resists, resist processing, resist structure, block copolymers, modelling

Manuscript submission deadline is 23 October 2015

Manuscripts of the special issues will be submitted and reviewed via the online Elsevier Editorial System (EES). After acceptance, articles will be processed and published with the standard Elsevier publishing timeline for each individual manuscript. Please submit papers directly using the [MEE journal submission web page](#) and select the appropriate special issue. The submission opens on 22 September, 2015.

Guest Editors

[Cornelis W. Hagen](#) (Delft University of Technology, The Netherlands)

[Paul F.A. Alkemade](#) (Delft University of Technology, The Netherlands)

Instructions for authors

- The standard submitted manuscripts are regular MEE publications (4-6 pages of final print).
- Review papers (7-10 pages) are encouraged from invited/plenary MNE speakers and leading members of the community. If you are not an MNE invited speaker and you wish to submit a review, contact [Evangelos Gogolides](#) (Editor-in-Chief, Microelectronic Engineering) or one of the Guest Editors with a proposal and outline.
- Highly novel work can be submitted as an *accelerated* publication (up to 4 pages) and will be given high priority.
- For all publications, we encourage you to include supplementary data and audio/video abstracts.
- For general enquiries, contact [Luigi Sasso](#), MNE Program Co-Chair.
- Please select the file type (regular paper, review paper, etc.) and choose the name of the special issue: **μ nP 2015**.

Your paper and associated supplementary information should comprise a complete, novel and full description of your work. Make sure that your paper is well-written, and supply additional information, videos, audios, etc. as on-line supplementary material to appear on the web, but not in the printed version (see instructions for authors). Your supplementary material will be available directly from ScienceDirect or Scopus.

Please note that the special issue manuscripts undergo the same high-standard review process as any other MEE manuscript. At least two reviews need to be in agreement per paper before decision, and the typical rejection rate is 50-60%. Therefore, make sure that both the technical content, and your presentation style and language, is of high quality, novel, unpublished, and not being submitted elsewhere. Please check also the [author guidelines](#).